17th of November	
08:30-08:45	Opening
08:45-09:30	**Dr. John S. Villarrubia** *National Institute of Standards and Technology, MD, USA* From electron-solid interactions to quantitative SEM metrology: testing the physics from yield to topography
09:30-10:00	**Dr. Eliška Mikmeková** *Institute of Scientific Instruments of the Czech Academy of Science (ISI) Brno, Czech Republic* Low-Energy Electron Microscopy of 2D Materials: From Graphene to Electron Microscopy Applications
10:00-10:30	Coffee
10:30-10:50	**Dr. Paul Cannon** *Advanced Research Center for Nanolithography (ARCNL), Amsterdam, The Netherlands* Optical Measurements of Electric Fields for Electron Microscopy Applications
10:50-11:10	**Mr. Giel T. B. Coemans** *Delft University of Technology, The Netherlands* Predicting SEM Charging Artifacts in Semiconductor Structures Using a Dynamic Charge Balance Model
11:10-11:30	**Dr. Leo Sala** *Heyrovský Institute of the CAS, Prague, Czechia* Electron microscopy of DNA nanostructures and their hybrid assemblies
11:30-11:50	**Industrial pitch:** HITACHI, BIENNE TECHNOLOGY, ThermoFisher SCIENTIFIC
11:50-13:20	Lunch
13:20-13:50	**Prof. Sense Jan van der Molen** *Leiden University, Leiden, The Netherlands* Investigating EUV-resists with low-energy electrons
13:50-14:10	**Dr. Fabian Holzmeier** *IMEC, Leuven, Belgium* More is not always better: Dissociative photoionization limits the EUV absorbing photoacid generator pentafluorophenyl triflate in photolithography
14:10-14:30	**Prof. Lisa McElwee-White** *Department of Chemistry, University of Florida, Gainesville, USA* Mechanism-Based Design, Synthesis, and Characterization of a Small Molecule Inorganic Photoresist Candidate for EUV Lithography
14:30-14:45	**Industrial pitch:** ASML, ZEISS Seeing beyond
14:45-15:15	Coffee
15:15-15:45	**Dr. Sven Christian Barth** *Goethe University Frankfurt, Frankfurt, Germany* From Molecule to Nanostructure by Direct-Write Nanofabrication: Fundamental Beam–Material Interactions and Precursor Design
15:45-16:05	**Dr. Jaroslav Kočišek** *Heyrovský Institute of the CAS, Prague, Czechia* Reactivity of Low-Energy Electrons and Ions with Molecular Clusters Relevant to Nano-Manufacturing
16:05-16:25	**Mr. Nicolas P. Jochmann** *Goethe University Frankfurt, Germany* Precursor development for charged particle deposition: Case studies based on Nb and Ta
16:45-18:45	**Poster session opening** Posters are on display throughout the conference